

Title (en)

SELF-STOPPING POLISHING COMPOSITION AND METHOD FOR BULK OXIDE PLANARIZATION

Title (de)

SELBSTSTOPPENDE POLIERZUSAMMENSETZUNG UND VERFAHREN ZUR OXIDMASSENPLANARISIERUNG

Title (fr)

COMPOSITION DE POLISSAGE À AUTO-ARRÊT ET PROCÉDÉ DE PLANARISATION D'OXYDE EN MASSE

Publication

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Application

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Abstract (en)

[origin: WO2018194792A1] The invention provides a chemical-mechanical polishing composition comprising an abrasive, a self-stopping agent, an aqueous carrier, and optionally, a cationic polymer, and provides a method suitable for polishing a substrate.

IPC 8 full level

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